Attorney Docket No.: Q88089

AMENDMENT UNDER 37 C.F.R. § 1.111 Application No.: 10/537,496

AMENDMENTS TO THE CLAIMS

This listing of claims will replace all prior versions and listings of claims in the application:

LISTING OF CLAIMS:

- (currently amended): A method of subjecting a glass preform to processing by tensile forces in a furnace to produce a glass product of predetermined shape, according to which said method comprising
 - introducing at least a part of the glass preform is introduced into the furnace through an inlet opening,
 - heating a portion of the glass preform introduced into the furnace is heated to a temperature above the softening point of the glass preform,
 - subjecting the heated portion of the glass preform is subjected to tensile forces in a
 drawing direction to process the preform into the predetermined shape,
 - drawing the portion of the preform which has been processed into the predetermined
 shape is drawn-from the furnace through an outlet opening, and
 - flushing the heated portion of the preform and at least a part of the processed portion of
 the preform are flushed-in the furnace with inert gas which is being fed into the furnace,

characterized by

- maintaining the-a concentration of gaseous impurities in the furnace essentially on-the same level as athe concentration of the same impurities in the inert gas fed into the furnace,
- establishing a diffusion barrier against the <u>an</u> inflow of undesired gaseous

Attorney Docket No.: Q88089

AMENDMENT UNDER 37 C.F.R. § 1.111

Application No.: 10/537,496

eomponents impurities from the ambient air, driven by the forces of diffusion, by generating a barrier flow of inert gas in at least one opening selected from said inlet opening and said outlet opening of the furnace, said barrier flow having a direction of flow, which is generally opposite to the direction of the diffusion impurities.

- (original): The method according to claim 1, wherein the furnace comprises an elongated furnace chamber having a vertical central axis, said diffusion barrier being established in the inlet opening, which is located in the upper end of the elongated furnace chamber.
- (currently amended): The method according to claim 1, wherein a-the diffusion barrier is
 established in the inlet opening of the glass preform, in the inlet opening of the inert gas feed
 and in the outlet opening of the processed preform.
- 4. (currently amended): The method according to claim 2, wherein there is gas flow through the inlet opening of the glass preform, which flow corresponds to the equation (2)

F1=F*C1/(C1+C2) (2)

wherein

F1 stands for the gas flow through the inlet opening,

F stands for the total gas flow,

C1 stands for the a conductance of the inlet opening and

C2 stands for the a conductance of the outlet opening.

AMENDMENT UNDER 37 C.F.R. § 1.111 Attorney Docket No.: O88089 Application No.: 10/537,496 5. (currently amended): The method according to claim 4, wherein the each of the conductances C1 and C2 are calculated from the equation (3) $C=K_{-}^{*}W^{*}H^{3}/L$, (3) wherein C stands for conductance, K is a constant at low pressure differences, W is the width of the opening, H is the height of the opening, and L is the length of the opening. 6. (currently amended): The method according to claim 1, wherein there is a flow of inert gas through the outlet opening, which flow is at least equal to the flow of gas caused by the a chimney effect through the inlet opening. 7. (currently amended): The method according to claim 6, wherein the flow of inert gas into the furnace is sufficient still to form, based on the gas distribution according to equation (2), a diffusion barrier at the outlet opening of the processed preform; wherein equation (2) has the formula: (2) F1=F*C1/(C1+C2+C3) wherein F1 stands for the gas flow through the inlet opening, F stands for the total gas flow,

C1 stands for a conductance of the inlet opening and

Application No.: 10/537,496

C2 stands for a conductance of the outlet opening,

C3 stands for the purge of flow of the intermittent space.

8. (original): The method according to claim 7, wherein the outlet opening will allow for more

free flow of gas than the inlet opening to direct most of the inert gas flow fed into the furnace

through the outlet opening.

9. (previously presented): The method according to claim 3, wherein the conductance of the

outlet opening is greater than the conductance of the inlet opening.

10. (previously presented): The method according to claim 1, wherein the inert gas fed into the

furnace is equal to or greater than the flow of gas caused by the chimney effect + 1 SLM, in

particular chimney effect + 5 SLM.

11. (previously presented): The method according to claim 1, wherein the glass preform is

subjected to tensile drawing in order to stretch the preform into a shape suitable for post-

processing like drawing of optical fibres.

12. (previously presented): The method according to claim 1, wherein the glass preform is

subjected to drawing of optical fibre.

Attorney Docket No.: Q88089

AMENDMENT UNDER 37 C.F.R. § 1.111

Application No.: 10/537,496

13. (currently amended): The method according to claim 12, wherein the clearance between the

 \underline{an} exterior diameter of the glass preform and \underline{the} - \underline{an} inlet opening diameter is 0.1-10 mm for an

80 mm preform.

14. (original): The method according to claim 12, wherein there is a barrier flow along a barrier

distance of 0.5 to 100 mm.

15. (previously presented): The method according to claim 1, wherein the furnace comprises a

graphite induction furnace.

16. (currently amended): The method according to claim 1, comprising rotating the glass

preform about its central axis during heat-processingsaid heating in the furnace.

17. (withdrawn-currently amended): An apparatus for heating of glass performs which are

processed by tensile forces into a glass product of predetermined shape, comprising

- a furnace body having a jacket defining an elongated furnace chamber with an at least

essentially circular cross-section perpendicular to the central axis of the chamber,

- a first opening at one end of the chamber for receiving one end of a glass preform, which

is to be processed,

- a second opening at an opposite end of the chamber for withdrawal of the processed glass

product,

- graphite heating resistances mounted to the furnace chamber to provide for induction

Application No.: 10/537,496

heating of the glass preform in the furnace, and

- feed nozzles connected to at least the first opening of the chamber for introducing

protective gas into the furnace chamber,

e haracterized by

- a first diffusion barrier zone at the first opening for preventing inflow of undesired

gaseous componentsimpurities from the ambient air, driven by the forces of diffusion,

into the furnace chamber during heating of the glass preform.

18. (withdrawn): The apparatus according to claim 17, wherein there is a second diffusion

barrier zone at the second opening of the furnace chamber.

19. (withdrawn): The apparatus according to claim 17, wherein a nozzle for feed of protective

gas is connected to both the first and the second openings and, optionally, also to an opening

formed in the jacket of the furnace chamber at a point between the first and the second openings.

20. (withdrawn): The apparatus according to claim 17, wherein the apparatus is adapted for

heating of a glass preform subjected to drawing of optical fibre.

21. (withdrawn): The apparatus according to claim 20, wherein the clearing between the exterior

diameter of the glass preform and the first opening diameter is 0.1 - 10 mm for an 80 mm

preform.

Application No.: 10/537,496

22. (withdrawn): The apparatus according to claim 21, wherein the each barrier zone comprises

a length of the furnace chamber amounting to 0.5 to 100 mm, along which a barrier flow of

protective gas can be arranged.

23. (withdrawn): The apparatus according to claim 17, wherein the barrier zone comprises a

zone of essentially laminar gas flow.

24. (withdrawn): The apparatus according to claim 23, wherein the barrier zone is formed above

the feed nozzles of the protective gas.

25. (withdrawn): The apparatus according to claim 17, wherein the barrier zone is defined by the

clearance between a glass preform and the opening of the furnace.

26. (withdrawn): The apparatus according to claim 25, wherein the difference between the

external diameter of the glass preform and inner diameter of the opening is in the range of 0.5 to

15 mm.

27. (withdrawn): The apparatus according to claim 23, wherein the barrier zone has a length

parallel to the central axis of the furnace tube amounting to about 10 to 1000 mm, preferably

about 15 to 150 mm.

Application No.: 10/537,496

28. (withdrawn-currently amended): A process for heat-treatment of glass substrates, in which

method the glass substrate is placed in a first gas space of a heat treatment zone, surrounded by a

second, ambient gas space, said heat treatment zone being provided with at least one gas conduit

interconnecting the first and the second gas spaces, e haracterized characterized by

forming a diffusion barrier in the at least one gas conduit interconnecting the gas space inside the

heat treatment device with the ambient atmosphere to seal off the conduit against flow of gas in

at least one direction through the conduit.

29. (withdrawn-currently amended): The process according to claim 28, comprising establishing

a diffusion barrier against the inflow or outflow of undesired gaseous components impurities

from or to the ambient air, driven by the forces of diffusion, by generating a barrier flow of inert

gas in at least one said gas conduit, said barrier flow having a direction of flow, which is

generally opposite to the direction of the diffusion.

30. (withdrawn): The process according to claim 28, comprising establishing a diffusion barrier

in each of the gas conduits interconnecting the first and the second gas spaces.

31. (withdrawn): The process according to claim 28, wherein the heat treatment comprises

preform processing by Modified Chemical Vapour Deposition in an MCVD lathe.

Application No.: 10/537,496

32. (withdrawn): The process according to claim 28, wherein the heat treatment comprises

preform processing in a sintering furnace.

33. (withdrawn): The process according to claim 28, wherein the diffusion barrier is established

at a gas conduit comprising a rotary joint.

34. (withdrawn): The process according to claim 33, wherein the rotary joint is a non-contacting

joint.